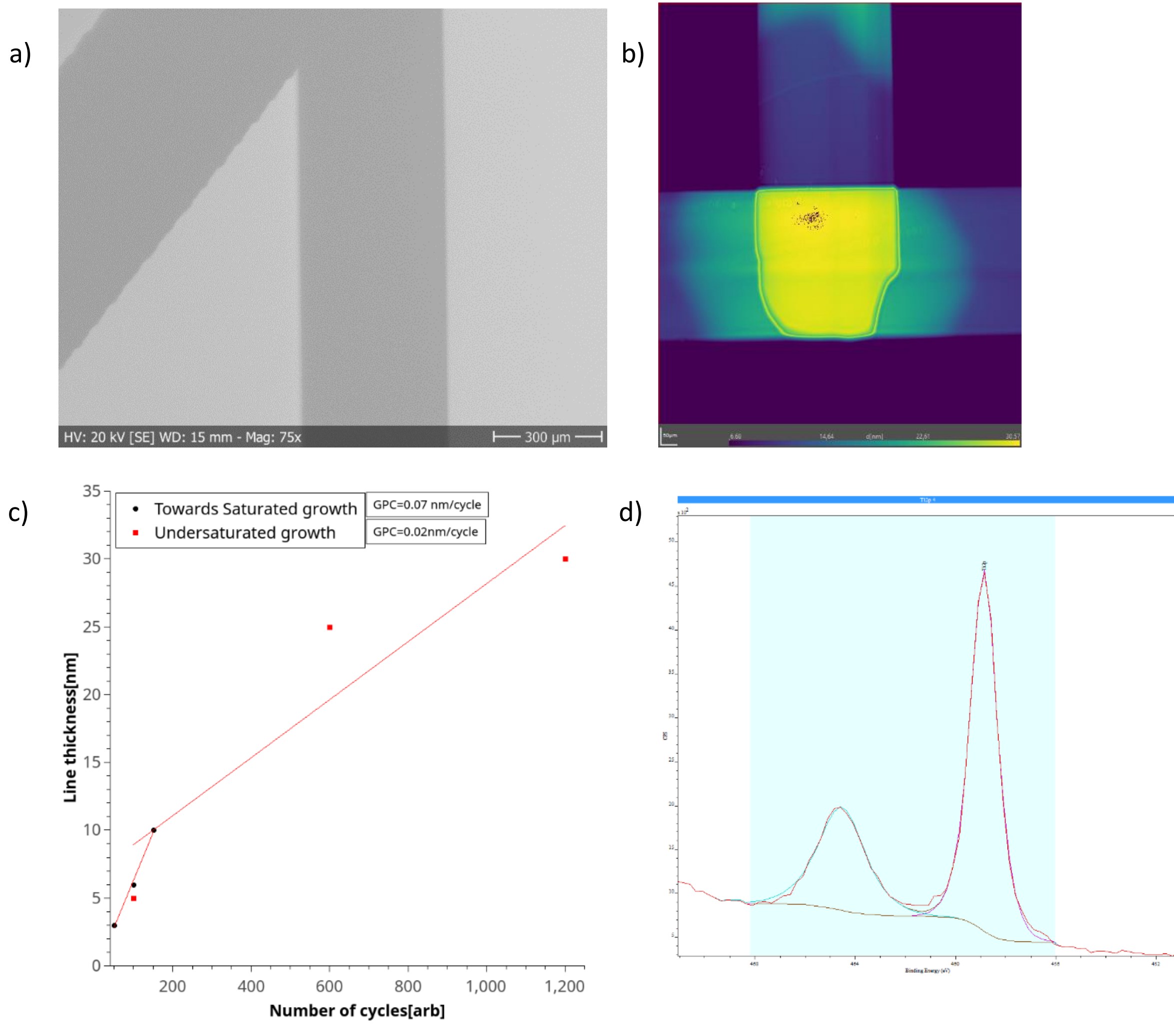

Figure 1: a) SEM of line pattern deposited on 200nm thermal SiO_2. b) Imagining ellipsometry of two crossing lines, the cross point as predicted being twice as thick. c) Initial undersaturated growth, measured by AFM. d) XPS as measured in the middle of the line, showing clear TiO_2 presence.

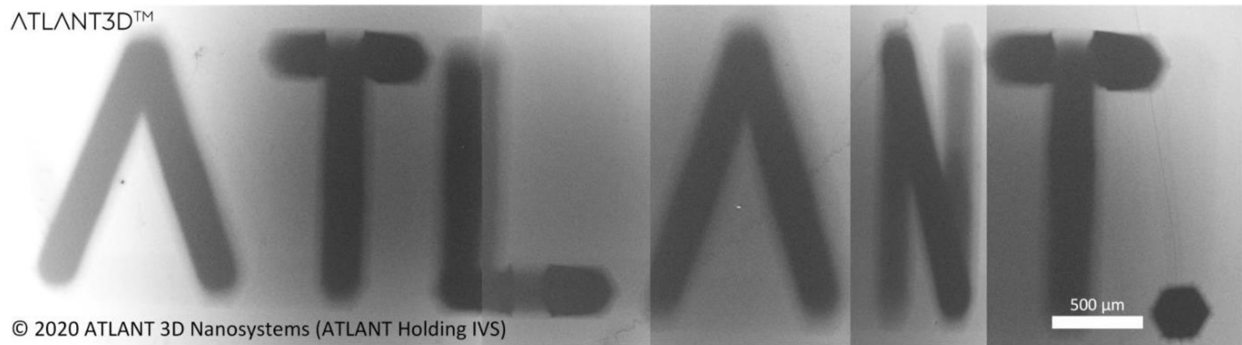

Figure 2: Example of a large pattern creation.